

ABSTRACT

A component for plasma processing apparatus includes a base member and a thermal-sprayed film on a surface of the base member. The surface of the
5 base member includes a main surface and a recess descending from the main surface of the base member at a position overlapping a distal edge portion of the thermal-sprayed film. The thermal-sprayed film includes a first thermal-sprayed film formed as a
10 continuous film over the main surface of the base member and a part of a region inside the recess, and a second thermal-sprayed film including a material different from the first thermal-sprayed film, and the second thermal-sprayed film being formed as a
15 continuous film over the first thermal-sprayed film to cover the first thermal-sprayed film and over another part of the region inside the recess not covered by the first thermal-sprayed film.

20 Fig. 3